

ATTORNEY DOCKET NO.: 0492611-0503 (MIT 10296)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Stellacci, et al.

Examiner:

Serial No.:

10/688,867

Art Unit:

Filing Date:

October 17, 2003

Title:

NANOCONTACT PRINTING

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

TRANSMITTAL LETTER

Enclosed are the following documents:

- 1. Form PTO-1449 (4 pages);
- 2. Information Disclosure Statement (6 pages);
- 3. Cited Art (51); and
- 4. Return Postcard

If any additional fees are required to be paid or if any overpayment has been made, please charge same to Deposit Account No. 03-1721.

Respectfully submitted,

Theresa A. Devlin

Registration No. 45,361

Choate, Hall & Stewart Exchange Place 53 State Street Boston, MA 02109 (617) 248-5000

Dated: January 28, 2004

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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner For Patents, P.O. Box 1450, Alexandria, VA 22313

Janely Laccocia

ATTORNEY DOCKET NO.: 0492611-0503 (MIT 10296)

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STATEMENT

Pursuant to the duty of disclosure under 37 C.F.R. §§1.56, 1.97 and 1.98, Applicant requests consideration of this Information Disclosure Statement.

Type of Statement

The present Information Disclosure Statement is:

[X] An original Information Disclosure Statement; or

[] A supplemental Information Disclosure Statement.

Certificate of Mailing

I certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to Commissioner for Patents, P.Q7 Box 1450, Alexandria, VA 22313-1450.

Date

Signature

Sandra Saccocia

Typed or Printed Name of person signing certificate

Compliance with 37 CFR § 1.97

The present Information Disclosure Statement is being filed:

[X]	Pursuant to 37 CFR § 1.97(b); no fee or certification is required:				
	[]	Withi	n three months of the filing date of a national application other than		
		a cont	tinued prosecution application under § 1.53(d);		
	[]	Withi	n three months of the date of entry of the national stage as set forth		
		in § 1 .	.491 in an international application;		
	[X]	Befor	e the mailing of a first Office action on the merits; or		
	[]	Befor	e the mailing of a first Office action after the filing of a request for		
		contin	nued examination under § 1.114.		
[]	Pursuant to 37 CFR § 1.97(c) after the dates listed above but before the mailing				
	date of any of a final action under § 1.113, a notice of allowance under § 1.311, or				
	an act	ion that	otherwise closes prosecution in the application; Applicant hereby		
	either	either:			
	[]	Certifies that either:			
		[]	each item of information contained in the information disclosure		
			statement was first cited in any communication from a foreign		
			patent office in a counterpart foreign application not more than		
			three months prior to the filing of the information disclosure		
			statement; or		
		[]	That no item of information contained in the information		
			disclosure statement was cited in a communication from a foreign		
			patent office in a counterpart foreign application, and, to the		
			knowledge of the person signing the certification after making		

reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in § 1.56(c) more than three months prior to the filing of the information disclosure statement.; or

			the information disclosure statement.; or
	[]	Includ	les herewith the fee set forth in § 1.17(p).
[] Pursuant to 37 CFR § 1.97(d), after the mailing date of any final a		7 CFR § 1.97(d), after the mailing date of any final action under	
	§ 1.11	3 , a noti	ice of allowance under § 1.311, or an action that otherwise closes
	prosec	ution in	the application; Applicant hereby both:
	[]	Certifi	ies that either:
		[]	each item of information contained in the information disclosure
			statement was first cited in any communication from a foreign
			patent office in a counterpart foreign application not more than
			three months prior to the filing of the information disclosure
			statement; or
		[]	That no item of information contained in the information
			disclosure statement was cited in a communication from a foreign
			patent office in a counterpart foreign application, and, to the
			knowledge of the person signing the certification after making
			reasonable inquiry, no item of information contained in the
			information disclosure statement was known to any individual
			designated in § 1.56(c) more than three months prior to the filing of
			the information disclosure statement.; and

[] Includes herewith the fee set forth in § 1.17(p).

Content of the Information Disclosure Statement

Applicant hereby makes of record in the above-identified application the reference(s) listed on the attached form PTO-1449 (modified). The order of presentation of the references should not be construed as an indication of the importance of the references.

Applicant includes copies of references as indicated below:

[X]	A copy of each cited reference not indicated with an asterisk is included;
[]	Copies of references indicated with an asterisk on the attached form PTO-1449
	are not included pursuant to 37 CFR § 1.98(d) because they were previously
	provided to the United States Patent Office in an Information Disclosure
	Statement that complies with 37 CFR § 1.98(a)-(c) and was submitted in the
	following patent application that is relied upon in the present case for an earlier
	effective filing date under 35 USC § 120:

Serial Number	Filing Date	Status

[] Copies of English translations of one or more non-English references are included.

Applicant hereby makes the following additional information of record in the aboveidentified application:

Applicant certifies that the Information Disclosure Statement either:

- [X] Does not contain non-English language citations;
- [] Does contain non-English language citations, of which the following is a concise explanation:
- [] Includes one or more translations of a non-English citation.

Remarks

The submission of this Information Disclosure Statement should not be construed as a representation that a search has been made.

The submission of this Information Disclosure Statement shall not be construed to be an admission that the information cited in the statement is, or is considered to be, material to patentability as defined in § 1.56(b).

The submission of this Information Disclosure Statement shall not be construed as a representation that the information cited in the Statement is, or is considered to be, in fact, prior art as defined by 35 U.S.C. §102.

It is respectfully requested that:

- 1. The Examiner consider completely the cited information, along with any other information, in reaching a determination concerning the patentability of the present claims;
- 2. The enclosed form PTO-1449 be signed by the Examiner to evidence that the cited patent(s) and publication(s) has (have) been fully considered by the Patent and Trademark Office during the examination of this application; and
- 3. The citations for the patent(s) and publication(s) be printed on any patent which issues from this application.

Notwithstanding any statements by Applicants, the Examiner is urged to form his or her own conclusions regarding the relevance of the cited reference(s).

Respectfully submitted,

Dated: January 28, 2004

Theresa A. Devlin Registration No. 45,361

CHOATE, HALL & STEWART Exchange Place 53 State Street Boston, Massachusetts 02109 (617) 248-5000 (617) 248-4000

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IP.	E				
Form PDO-1449 (REV. 8-83)	Patent and Ti	nent of Commerce rademark Office	Atty. Docket: 0492611-0503 (MIT 10296)	In re Application No. 10/688,867	
INFORMATION	INFORMATION DISOLOSURE STATEMENT			al.,	
(Use severor heets if necessary)			Filing Date: October 17, 2003	Group:	
U.S. PATENT D	OCUMENTS	· Section ·			
Examiner's Initials	U.S. Patent No.	Applicant	Issue Date	Class Subclass	
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FOREIGN PATI	ENT DOCUMENTS				
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Initials				Yes No	
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/Nelson Yang/

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(RE,V. 8-83)	Patent and Trademark Office	0492611-0503 (MIT 10296)	10/688,867	
	N DISCLOSURE STATEMENT	Applicant: Stellacci, et al.,		
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/Nelson Yang/

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/Nelson Yang/

04/17/2008

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(RE.V. 8-83)	Patent and Trademark Office	0492611-0503	10/688,867	
		(MIT 10296)		
INFORMATION DISCLO		Applicant: Stellacci, et al.,		
(Use several sheets if necessary)		Filing Date:	Group:	
	<u> </u>	October 17, 2003		
EXAMINER A JAN 3 0 2004 B /Nelson Yang/ DATE CONSIDERED 04/17/2008				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to				

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applicant.